

ABSTRACT OF DISCLOSURE

In order to more accurately control the radiation characteristics of microwaves to improve the controllability of processing in radial and

- 5 circumferential directions of an article, there are disclosed a microwave applicator and a plasma processing apparatus using the applicator, which comprise a circular waveguide having a surface provided with a plurality of slots for radiating microwaves,
- 10 wherein the centers of the plurality of slots are offset in a direction parallel to the surface with respect to the center of the circular waveguide.